

IN THE CLAIMS

Please amend original claims ~~3~~, ~~4~~, ~~7~~, ~~8~~, ~~11~~, ~~12~~, ~~14~~, ~~15~~, ~~17~~,
18, 20 and 21 as follows:

~~3. (Amended) A process as claimed in claim 1 wherein each molecule of the gaseous oxygen scavenger is capable of combining with more than one atom of oxygen.~~

~~4. (Amended) A process as claimed in claim 1 wherein the gaseous oxygen scavenger is a hydrocarbon.~~

~~7. (Amended) A process as claimed in claim 1 wherein the coating atmosphere contains the gaseous oxygen scavenger in an amount that is sufficient to alleviate oxidation and/or degradation of the reflective metal layer.~~

~~8. (Amended) A process as claimed in claim 1 wherein the coating atmosphere contains a measurable amount of oxygen and contains the gaseous oxygen scavenger in an amount that exceeds 15 mol% of the amount of oxygen.~~

~~11. (Amended) A process as claimed in claim 1 wherein the reflective metal layer is a silver layer.~~

~~#3~~ Sub
~~CAA#~~ BI
12. (Amended) A process as claimed in claim 1 wherein the reflective metal layer has a thickness in the range 5 to 30 nm.

~~#4~~ Sub
14. (Amended) A process as claimed in claim 1 wherein the sheet resistance of the reflective metal layer is below 12 Ω /square.

Sub
BI
15. (Amended) A process as claimed in claim 1 wherein the coating atmosphere contains a measurable amount of oxygen and the sheet resistance of the reflective metal layer deposited in the coating atmosphere is below 12 Ω /square.

~~#5~~ Sub
BI
17. (Amended) A process as claimed in claim 1 wherein the low pressure deposition process for depositing the reflective metal layer is sputtering.

18. (Amended) A process for production of a coated substrate as claimed in claim 1 that additionally comprises depositing a metal oxide anti-reflection layer by a low pressure deposition process before depositing the reflective metal layer.